

**In The Claims:**

Please amend the claims as follows:

1. (Currently Amended) An optical interference display unit at least comprising:
  - a first electrode;
  - a second electrode, in parallel with the first electrode and comprising:
    - a first material layer; and
    - a ~~second material~~ conductive layer on the material layer; and
  - a support structure partially covered by the second electrode and supporting a edge of the second electrode;

wherein ~~at least one material for forming the first material layer and the second material layer is a conductive material~~ a material of the conductive layer is more difficult etched than a material of the material layer.
2. (Original) The optical interference display unit of claim 1, wherein the optical interference display unit is located on a substrate.
3. (Original) The optical interference display unit of claim 2, wherein the substrate is a transparent substrate.
4. (Original) The optical interference display unit of claim 1, wherein a material of the first electrode is a conductive transparent material.
5. (Original) The optical interference display unit of claim 4, wherein the conductive transparent material is indium tin oxide (ITO), indium zinc oxide (IZO), or indium oxide (IO)
6. (Original) The optical interference display unit of claim 1, wherein the second electrode is a deformable electrode.

7. (Original) The optical interference display unit of claim 1, wherein the second electrode is a movable electrode.

8. (Original) The optical interference display unit of claim 1, wherein a material for forming the support structure is selected from a group consisting of positive photoresist, negative photoresist, acrylic resin and epoxy resin.

9. (Currently Amended) The optical interference display unit of claim 1, wherein the ~~first~~ material layer is made from a conductive material ~~and the second material layer is made from metal or dielectric material.~~

10. (Currently Amended) The optical interference display unit of claim 1, wherein the ~~first~~ material layer is made from ~~metal or dielectric material and the second material layer is made from a conductive material.~~

11. (Currently Amended) The optical interference display unit of claim 4 9, wherein a material for forming the material layer is aluminum, chromium, cobalt, copper, silicon nitride or silicon oxide.

12. (Currently Amended) The optical interference display unit of claim 1, wherein a material for forming the ~~second material~~ conductive layer is aluminum, chromium, cobalt, copper, silicon nitride or silicon oxide.

13. (Canceled)